

Molecular Imprints Inc. Launches First S-FIL™ Tool at the Nanoimprint and Nano Technology Conference

Imprio™ 100 is the first of its kind Step and Flash Imprint Lithography (S-FIL) System

Austin, TX., December 9, 2002—Molecular Imprints Incorporated (MII) today announced it will launch its first Step and Flash Imprint Lithography (S-FIL) system, Imprio 100, at the Nanoimprint and Nano Technology (NNT) conference and exhibit being held December 11-13 at the San Francisco Marriot Hotel.

Designed for sub-100 nanometer features, the Imprio 100 is a lithographic tool for creating compound semiconductors, nano-devices, MEMS, photonic and optical communications components, and semiconducting devices. The system uses a simple step and repeat process at about one-tenth the cost of traditional projection systems. The tool is unique in that it operates in a room temperature and low pressure environment, further reducing the overall cost-of-operation. This first generation tool is manual and designed for small volume manufacturing, R&D, and process, material and template development and is capable of handling wafer sizes from 2 to 8 inches. The next generation system, expected in 2004, will be capable of throughputs that will meet production volume expectations.

“We are offering the industry a low cost lithography alternative that is already printing images that exceed the International Technology Roadmap for Semiconductors (ITRS) roadmap,” said Norman E. Schumaker, President and CEO of Molecular Imprints. “We are confident about our ability to replicate exactly the features on the template and give lithographers the performance they require.”

S-FIL technology will be the subject of at least four presentations and a poster session at the NNT conference this week. For more information visit www.davincinetbook.com/nnt/.

Editors interested in learning more about this new product and technology, or visiting us at the NNT conference and exhibition, may contact Karen Hopkins at MII via phone: +408/417-0281; email:khopkins@militho.com. High resolution photos are available upon request.

About Molecular Imprints Incorporated

MII was founded in February, 2001 to design, develop, manufacture and support imprint lithography systems to be used by semiconductor device manufacturers. In 2001 the company received SBIR and DARPA contracts. Molecular Imprints closed its first round of funding in February, 2002 and was awarded additional DARPA contracts in March and August, 2002. For more information visit www.militho.com.

Imprint Lithography

Step and Flash Imprint Lithography (S-FIL) is a bi-layer approach using a low-viscosity, UV-curable liquid etch barrier deposited on an underlying transfer layer. The template is rigid and transparent allowing for UV curing of

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the etch barrier and the adaptation of traditional layer-to-layer alignment techniques. This lithography approach may be the enabling technology for research applications in the areas of nano-devices, MEMS and optical communications components and devices.

Patented Technology

Molecular Imprints has exclusive license to develop and use S-FIL technology which was invented at the University of Texas at Austin under the direction of Professors Grant Willson and S.V. Sreenivasan for the lifetime of the patents.

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